	Application No.	Applicant(s)	
Notice of Allowability	10/620,129	HAUER ET AL.	
	Examiner	Art Unit	× 1
	THUY V. TRAN	2821	
The MAILING DATE of this communication at All claims being allowable, PROSECUTION ON THE MERITS herewith (or previously mailed), a Notice of Allowance (PTOL NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATEN of the Office or upon petition by the applicant. See 37 CFR 1	S IS (OR REMAINS) CLOSED in thi -85) or other appropriate communic T RIGHTS. This application is subj	s application. If not included ation will be mailed in due co	Jurse <b>THIS</b>
1. 🖾 This communication is responsive to 7/15/2003 & Inter	view held on 05/05/2004.		
2. The allowed claim(s) is/are <u>1-8</u> .			
3. The drawings filed on are accepted by the Exam	niner.		
4. ☐ Acknowledgment is made of a claim for foreign priorit  a) ☐ All b) ☐ Some* c) ☐ None of the:  1. ☐ Certified copies of the priority documents h	nave been received.		
2. Certified copies of the priority documents h			
3. Copies of the certified copies of the priority	documents have been received in	this national stage applicatio	n from the
International Bureau (PCT Rule 17.2(a)).	*		
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DAT noted below. Failure to timely comply will result in ABANDC THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be su INFORMAL PATENT APPLICATION (PTO-152) which	ONMENT of this application.  Ibmitted. Note the attached EXAMIN	NER'S AMENDMENT or NO	
6. 🛮 CORRECTED DRAWINGS ( as "replacement sheets") i	must be submitted.		
(a) ☐ including changes required by the Notice of Draftsp		TO-948) attached	
1)  hereto or 2)  to Paper No./Mail Date			
(b) including changes required by the attached Examir Paper No./Mail Date 05052004.	ner's Amendment / Comment or in the	ne Office action of	
Identifying Indicia such as the application number (see 37 CF each sheet. Replacement sheet(s) should be labeled as such	R 1.84(c)) should be written on the dr in the header according to 37 CFR 1.	awings in the front (not the ba	ack) of
<ol> <li>DEPOSIT OF and/or INFORMATION about the de attached Examiner's comment regarding REQUIREMEN</li> </ol>	posit of BIOLOGICAL MATERIA NT FOR THE DEPOSIT OF BIOLOG	AL must be submitted. Not GICAL MATERIAL.	e the
Attachment(s)			
Notice of References Cited (PTO-892)	5. Notice of Inform	al Patent Application (PTO-1	52)
2. Notice of Draftperson's Patent Drawing Review (PTO-94			J2) .
B. ☐ Information Disclosure Statements (PTO-1449 or PTO/S Paper No./Mail Date	Paper No /Mail	Date <u>05052004</u> .	
Examiner's Comment Regarding Requirement for Depos	it 8. 🛛 Examiner's State	ement of Reasons for Allowa	nce .
of Biological Material	9. ⊠ Other <u>See Conti</u>		,
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		THUY V. TRAN <b>/</b> Examiner Art Unit: 2821	

Art Unit: 2821

## **DETAILED ACTION**

This is a response to the Applicants' filing on July 15<sup>th</sup>, 2003 and the interview held on May 5<sup>th</sup>, 2004. In virtue of this filing, claims 1-8 are currently presented in the instant application.

### Examiner's Amendment

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Benjamin Hudson, Jr. on May 5<sup>th</sup>, 2004. The Examiner's amendment includes:

### • Amendment to the title:

Change the original title to --AN IMPROVED RF POWER CONTROL DEVICE FOR RF PLASMA APPLICATIONS--;

## • Amendment to the Abstract:

Line 1, change "method" to --device--;

Line 11, change "Plasma" to --plasma--; and

Line 12, insert --device and -- between "control" and "methods";

# • Amendment to the claims:

Claim 1, line 11, change "are" to --is--;

Claim 1, line 18, change "deliver" to --delivered--;

Claim 5, line 2, change "a" (first occurrence) to --an--;

Art Unit: 2821

Claim 5, line 11, change "are" to --is--;

Claim 5, line 12, change "forward and reflected signal mixers" to --a first mixer--;

Claim 5, line 19, insert -- a-- between "to" and "second";

Claim 5, line 20, insert --to-- between "connected" and "the"; and replace "forward

and reflected signal mixers" with --first mixer--;

Claim 5, line 26, change "deliver" to --delivered--; and

Claim 6, line 3, change "forward and reflected signal mixers" to --first mixer--;

### Amendment to the specification:

Page 3, line 16, change "10" to --10'--;

Page 3, line 22, change "20" to --20'--;

Page 3, line 23, change "22" to --22'--; change "24" to --24'--; and change "26" to --26'--;

Page 3, line 24, change "30" to --30'--; and change "32" to --32'--;

Page 4, line 16, change "30, 32" to --30', 32'--:

# Amendment to the drawings:

In FIGURE 2:

Change "10" to --10'--;

Change "18" to --output to matching network and plasma--;

Change "20" to --20'--;

Change "22" to --22'--;

Change "24" to --24'--:

Change "26" to --26'--;

Art Unit: 2821

Change "30" to --30'--;

Change "32" to --32'--;

In FIGURE 3:

Change "output" to --output to matching network and plasma--; and

In FIGURE 4:

Change "output" to --output to matching network and plasma--;

Insert "REFL" on the opposite side of "FWD".

### Allowable Subject Matter

2. Claims 1-8 are allowed.

### Reasons for Allowance

- 3. The following is an examiner's statement of reasons for allowance:
  - Prior art fails to disclose or fairly suggest:
    - A VHF generator for delivering RF power to a plasma comprising (1) each of the sampled forward and reflected signals is connected to mixers for mixing with an intermediate frequency of an oscillator, (2) the mixed forward and reflected signals are passed through low-pass filters, (3) the filtered forward and reflected signals are connected to amplifiers and detectors, and (4) the detected forward and reflected signals are fed back to a power control circuit wherein the power delivered to the plasma is monitored without interference from spurious frequency signals generated by the plasma, in combination with the remaining claimed limitations as called for in independent claim 1 (claims 2-4 are allowed since they are dependent on claim 1);

A VHF generator for delivering RF power to a plasma comprising (1) a first oscillator connected to a second mixer for mixing a sampled output of the variable RF signal generator with a first intermediate frequency, (2) the output of the second mixer is connected to a first band pass filter and then connected to a third mixer for mixing with a second intermediate frequency of a second oscillator, (3) the output of the third mixer is connected to a second band-pass filter and connected to the first mixer, (4) the mixed forward and reflected signals are passed through low pass filters, (5) the filtered forward and reflected signals are connected to amplifiers and detectors, and (6) the detected forward and reflected signals are fed back to a power control circuit wherein the power delivered to the plasma is monitored without interference from spurious frequency signals generated by the plasma, in combination with the remaining claimed limitations as called for in independent claim 5 (claims 6-8 are allowed since they are dependent on claim 5).

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

#### Citation of relevant prior art

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Prior art Reyzelman et al. (U.S. Patent No. 6,703,080) discloses a method and apparatus for VHF plasma.

Art Unit: 2821

Prior art Chen et al. (U.S. Patent No. 6,472,822) discloses a pulsed RF power delivery for plasma processing.

Prior art Wilbur (U.S. Patent No. 6,020,794) discloses an RF plasma system.

Prior art Turner et al. (U.S. Patent No. 5,939,886) discloses a plasma monitoring and control method and system.

Prior art Barnes et al. (U.S. Patent No. 5,892,198) discloses a method and apparatus for controlling RF plasma processor.

Prior art Benjmin et al. (U.S. Patent No. 5,708,250) discloses an RF plasma processor.

Prior art Mavretic et al. (U.S. Patent No. 5,654,679) discloses an apparatus for matching a variable load impedance with an RF power generator impedance.

#### Inquiry

Any inquiry concerning this communication or earlier communications from the examiner should be directed to THUY V. TRAN whose telephone number is (571) 272-1828. The examiner can normally be reached on M-F (8:30 AM-6:00 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, DON K. WONG can be reached on (571) 272-1834. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Art Unit: 2821

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

THUY V. TRAN Examiner Art Unit 2821 Page 7

T.T. 05/05/2004

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